PECVD-SIO2	Date	wafer#	LPD count before	LPD after 5min pump down	LPD after SiO2 deposition	Thickness	Index
	5/9/12						
		wafer1	407	457			
		wafer2	550	594			
		wafer3	957	502			
		wafer4					
		wafer5					
	PM-5-9-2012						
		wafer1	302	608*			
		wafer2	482	487			
		wafer3	529	470			
		wafer4	1361		838	1142.48	1.458
		wafer5	1129		1166***	1071.59**	1.463
***Clean was not done prior this deposition							
** Wafer moved during deposition, not uniform color							
* Use N2 gun prior loading wafer-added some particles							
PECVD-SiO2	**Date**	**wafer#**	**LPD count before**	**LPD after 5min pump down**	**LPD after SiO2 deposition**	**Thickness**	**Index**
	5/24/12	wafer1	124	121	209	1077.3A	1.464
	PM-6-1-2012						
	6/4/12	wafer1	189	242			
		wafer2	106	104	121	1012.08A	1.456
		wafer3	237	298			
	6/15/12	wafer1	148	147	195	2920.03A	1.457